

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit 1752

In re application of : September 29, 2006
Wu-Song Huang et al. : Examiner: Geraldine V. Letscher
Serial No. : 10/537,259
Filed: May 31, 2005 : IBM Corporation
Title: High Sensitivity Resist Dept. 18G/Bldg, 300-482
Compositions For Electron-Based 2070 Route 52
Lithography : Hopewell Junction, NY
: 12533-6531

Amendment

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

The following amendment is submitted in response to the official action
dated June 29, 2006.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.